

FORM PTO-1449  
(Equivalent)

U.S. Department of Commerce  
Patent and Trademark Office

U.S. Application Serial No.  
09/506,425

Atty. Docket No.  
AM-3751

INFORMATION DISCLOSURE  
STATEMENT BY APPLICANT

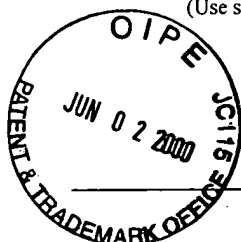
Sara Giordani  
Applicants

(Use several sheets if necessary)

February 17, 2000  
Filing Date

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U. S. PATENT DOCUMENTS

Examiner Initial	Document Number	Issue Date	Name	Class	Subclass	Filing Date If Appropriate
<u>Geo</u>	4,895,810	01/23/90	Meyer et al. ✓	431	41	
<u>Geo</u>	5,182,234	01/26/93	Meyer ✓	437	233	
<u>Geo</u>	5,229,315	07/20/93	Jun et al. ✓	437	67	
<u>Geo</u>	5,318,665	06/07/94	Oikawa ✓	156	643	
<u>Geo</u>	5,656,535	08/12/97	Ho et al. ✓	438	386	

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FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Country	Publication Date	Name	Class	Subclass	Translation If Appropriate
<u>Geo</u>	~EP 0272143	Europe	06/22/88	Wong et al.	H01L	21/306	
<u>Geo</u>	EP 0565212	Europe	10/13/93	Wong et al.	H01L	21/306	
<u>Geo</u>	~EP 0821409	Europe	01/28/98	Coronel	H01L	21/8242	
<u>Geo</u>	~EP 0822593	Europe	02/04/98	Haue et al.	H01L	21/8242	

Alfred Oha 1/26/02  
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

*See* M. Sato et al., "Effect of Gas Species on the Depth Reduction in Silicon Deep-Submicron Trench Reactive Ion Etching", *Jap. J. Appl. Physics*, Vol. 30, No. 7, pp. 1549 - 1555 (1991).

G. Yeom et al., "Polysilicon Etch Back Plasma Process Using HBr, Cl<sub>2</sub>, and SF<sub>6</sub> Gas Mixtures for Deep-Trench Isolation", *J. Electrochem. Soc.*, Vol. 139, No. 2, pp. 575 - 579 (1992).

U.S. Patent Application Serial No. 09/144,008, of Lill et al., filed August 31, 1998.

*See* U.S. Patent Application Serial No. 09/372,477, by Podlesnik et al., filed August 11, 1999.

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FORM 1-10  
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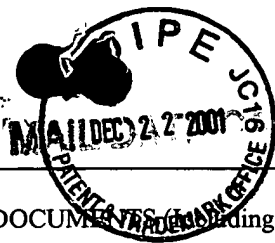
FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Publication Date	Name	Class	Subclass	Translation If Appropriate
<u>AW</u>	✓ EP 0727807	08/21/96	Hanawa et al.	H01J	37/32	
<u>AW</u>	✓ EP 0884401	12/16/96	Rossmann et al.	C23C	16/44	
<u>AW</u>	✓ EP 0908936	04/14/99	Muller et al.	H01L	21/306	
<u>AW</u>	✓ JP 58134445	08/10/83	Ogata Toshiaki	H01L	21/76	
<u>AW</u>	✓ JP 03203326	09/05/91	Nitta Sachiyo	H01L	21/302	
<u>AW</u>	✓ JP 05102142	04/23/93	Kamiide Koyo	H01L	21/3205	
<u>AW</u>	✓ JP 06077175	03/18/94	Kadomura Shingo	H01L	21/302	

Allen W. Olson  
Examiner

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OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, etc.)

*Due* -R. Pinto et al., "Reactive Ion Etching in SF<sub>6</sub> Gas Mixtures", *J. Electrochem Soc.*: SOLID-STATE SCIENCE AND TECHNOLOGY, Vol. 134, No. 1, pp. 165 - 175 (1987).

*file* / Copy of Search Report in corresponding International Patent Application No. PCT/US01/05194, mailed September 14, 2001.

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